## AMENDMENTS TO THE CLAIMS

Please amend the claims as follows.

1. (Currently Amended) A resist stripping equipment, comprising:

a first stripping solution tank in which resist stripping solution is preserved;

a plurality of ~~first~~ resist stripping chambers in which a substrate covered with resist is accommodated, wherein the plurality of resist stripping chambers are provided in communication with each other, and wherein the substrate is supplied from a first stage resist stripping chamber to a next stage resist stripping chamber;

a first spray which is connected to the first stripping solution tank and sprays the resist stripping solution into the resist in the first resist stripping chamber;

a first solution line which supplies the sprayed resist stripping solution from the first resist stripping chamber to the first resist stripping tank;

a gas line which supplies a mixed gas containing a resist stripping solution component from the first resist stripping chamber to outside;

a gas/liquid separation block which is connected to the gas line, and which separates the resist stripping solution component from the introduced mixed gas;

~~a second resist stripping chamber which is connected to the first resist stripping chamber and whereto the substrate is supplied from the first resist stripping chamber;~~

a second stripping solution tank in which resist stripping solution is preserved;

a second spray which is connected to the second stripping solution tank and sprays the resist stripping solution into the resist in the second resist stripping chamber;

a second solution line which supplies the sprayed resist stripping solution from the second resist stripping chamber to the second resist stripping tank;

a recovered resist stripping solution line which is connected to the gas/liquid separation block and supplies the separated resist stripping solution component to the second stripping solution tank; ~~and~~

a line which is connected to the second stripping solution tank and supplies the resist stripping solution to the first stripping solution tank;

a rinse chamber provided in communication with a last stage resist stripping chamber, wherein the substrate is supplied from the last stage resist stripping chamber to the rinse chamber, and wherein the rinse chamber is supplied with water;

a damper which is connected on the gas line;

a pressure switch which monitors an inner pressure of the rinse chamber and transmits to the damper a value travel signal; and

an inert gas supply unit which is connected to the rinse chamber and supplies inert gas into the rinse chamber.

2. (Previously Presented) The resist stripping equipment of claim 1, further comprising:

a separated gas supply unit which receives gas separated from the resist stripping solution component in the liquid/gas separation block and supplies the gas to a gas spout unit,

wherein at least one of the resist stripping chambers includes ~~a~~ the gas spout unit.

3. (Original) The resist stripping equipment of claim 2, wherein the gas spout unit is disposed facing the substrate.

4. (Cancelled)

5. (Cancelled)

6. (Cancelled)

7. (New) A resist stripping equipment, comprising:

a first stripping solution tank in which resist stripping solution is preserved;

a plurality of resist stripping chamber in which a substrate covered with resist is accommodated, wherein the plurality of resist stripping chambers are provided in communication with each other, and wherein the substrate is supplied from a first stage resist stripping chamber to a next stage resist stripping chamber;

a first spray which is connected to the first stripping solution tank and sprays the resist stripping solution into the resist in the first resist stripping chamber;

a first solution line which supplies the sprayed resist stripping solution from the first resist stripping chamber to the first resist stripping tank;

a gas line which supplies a mixed gas containing a resist stripping solution component from the first resist stripping chamber to outside;

a gas/liquid separation block which is connected to the gas line, and which separates the resist stripping solution component from the introduced mixed gas;

a second stripping solution tank in which resist stripping solution is preserved;

a second spray which is connected to the second stripping solution tank and sprays the resist stripping solution into the resist in the second resist stripping chamber;

a second solution line which supplies the sprayed resist stripping solution from the second resist stripping chamber to the second resist stripping tank;

a recovered resist stripping solution line which is connected to the gas/liquid separation block and supplies the separated resist stripping solution component to the second stripping solution tank;

a line which is connected to the second stripping solution tank and supplies the resist stripping solution to the first stripping solution tank;

a rinse chamber provided in communication with a last stage resist stripping chamber, wherein the substrate is supplied from the last stage resist stripping chamber to the rinse chamber, and wherein the rinse chamber is supplied with water;

a damper which is connected on the gas line;

a pressure switch which monitors an inner pressure of the last stage resist stripping chamber and transmits to the damper a value travel signal; and

an inert gas supply unit which is connected to the last stage resist stripping chamber and supplies inert gas into the last stage resist stripping chamber.